EE 434 Lecture 2

Basic Concepts

Review from Last Time

- Semiconductor Industry is One of the Largest Sectors in the World Economy and Growing
- All Initiatives Driven by Economic Opportunities and Limitations
- Rapidly Growing Device Count and Rapidly Shrinking Feature Sizes (Moore's Law?)
- Designers Must Handle Incredible Complexity Yet Work in Large Teams and Make Almost No Mistakes
- Understand the Big Picture and Solve the Right Problem

ITRS Technology Predictions

ITRS 2004 Supply Voltage Predictions



ITRS Technology Predictions

Minimum ASIC Gate Length



CAD Environment for Integrated Circuit Design

- Typical Tool Flow
 - (See Chapter 8 of Text)
- Laboratory Experiments in Course



VLSI Design Flow Summary

Digital Flow



VLSI Design Flow Summary Mixed Signal Flow (Digital Part)



VLSI Design Flow Summary

Mixed-Signal Flow (Analog Part)



VLSI Design Flow Summary

Mixed-Signal Flow (Analog-Digital Merger)



Comments

- The Analog Design Flow is often used for small digital blocks or when particular structure or logic styles are used in digital systems
- Variants of these flows are widely used and often personalized by a given company or for specific classes of circuits

Wafer



• very large number of die if die size is small

Feature Size

Feature size is the minimum lateral feature size that can be <u>reliably</u> manufactured





Often given as either feature size or pitch

Minimum feature size often identical for different features

What is meant by "reliably"

Yield is acceptable if a very large number of these features are made

If P is the probability that a feature is good

n is the number of features on an IC

Y is the yield

$$Y = P^{n}$$
$$\frac{\log_{e} Y}{n}$$

Example: How reliable must a feature be?

n=5E3

Y=0.9

$$P = e^{\frac{\log_e Y}{n}} = e^{\frac{\log_e 0.9}{5E3}}$$
 =0.999979

But is n=5000 large enough ?

More realistically n=5E9

$$P = e^{\frac{\log_e Y}{n}} = e^{\frac{\log_e 0.9}{5E3}} = 0.999999999979$$

Extremely high reliability must be achieved in all processing steps to obtain acceptable yields in state of the art processes

Feature Size

- Typically minimum length of a transistor
- Often minimum width or spacing of a metal interconnect (wire)
- Point of "bragging" by foundries

 Drawn length and actual length differ
- Often specified in terms of pitch
 - Pitch approximately equal to twice minimum feature size

Feature Size Evolution

Mid 70's	25µ
2005	90nm
2010	45nm
2020	20nm

$$1\mu = 10^3 nm = 10^{-6} m = 10^4 \text{ Å}^{\circ}$$







Actual Drain and Source at Edges of Channel



Smaller than Drawn Width and Length

Technology Nomenclature

- SSI Small Scale Integration 1-100
- MSI Medium Scale Integration 100-10³
- LSI Large Scale Integration 10³-10⁵
- VLSI Very Large Scale Integration 10⁵-10⁶

Any design in a process capable of incorporating a large number of devices is generally termed a VLSI design

Device and Die Costs

Consider the high-volume incremental costs of manufacturing integrated circuits

Example: Assume an 8" wafer in a 0.25µ process costs \$800

Determine the number of minimum-sized transistors that can be fabricated on this wafer and the cost per transistor. Neglect spacing and interconnect.

$$n_{trans} \cong \frac{A_{wafer}}{A_{trans}} = \frac{\pi (4in)^2}{(0.25\mu)^2} = 5.2E11$$
$$C_{trans} = \frac{C_{wafer}}{n_{trans}} = \frac{\$800}{5.2E11} = \$15.4E - 9$$

Note: the device count may be decreased by a factor of 10 or more if Interconnect and spacing is included but even with this decrease, the cost per transistor is still very low!

Device and Die Costs

 $C_{per unit area} \cong \$2.5 / cm^2$

Example: If the die area of the 741 op amp is 1.8mm², determine the cost of the silicon needed to fabricate this op amp

$$C_{741} = \$2.5 / cm^2 \bullet (1.8mm^2) \cong \$.05$$

Actual integrated op amp will be dramatically less if bonding pads are not needed

Size of Atoms and Molecules in Semiconductor Processes

Silicon:	Average Atom Spacing	2.7 Å
	Lattice Constant	5.4 Å
S _i O ₂	Average Atom Spacing	3.5 Å
	Breakdown Voltage	5 to 10 MV/cm = 5 to 10 mV/Å
Air		20KV/cm

Physical size of atoms and molecules place fundamental limit on conventional scaling approaches